

10797723_CLS.txt
Most Frequently Occurring Classifications of Patents Returned
From A Search of 10797723 on January 26, 2005

Original Classifications

4 250/251
3 204/298.04
3 250/423R
3 250/427
3 313/359.1
2 60/202
2 204/192.11
2 250/492.21
2 315/111.21
2 315/111.81
2 315/111.91

Cross-Reference Classifications

8 250/423R
8 315/111.81
6 313/231.31
6 315/111.41
5 315/111.31
4 204/298.16
4 313/359.1
4 313/362.1
4 313/363.1
3 204/298.19
3 250/398
3 315/111.21
3 376/130
3 428/408
3 428/694TC
2 204/192.11
2 204/298.36
2 250/251
2 250/305
2 250/397
2 250/492.2
2 250/492.21
2 313/231.41
2 313/360.1
2 313/361.1
2 315/111.61
2 315/111.91
2 376/147
2 427/527
2 427/580
2 428/336
2 976/DIG 437

Combined Classifications

11 250/423R
10 315/111.81
7 313/359.1
6 250/251
6 313/231.31
6 315/111.41
5 313/363.1
5 315/111.21
5 315/111.31
4 204/192.11
4 204/298.04

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4 204/298.16
4 250/427
4 250/492.21
4 313/362.1
4 315/111.91
4 376/130
4 428/408
3 60/202
3 204/298.19
3 250/398
3 313/360.1
3 427/580
3 428/336
3 428/694TC
2 118/723I
2 156/345.39
2 204/298.36
2 250/305
2 250/397
2 250/492.2
2 313/231.41
2 313/361.1
2 315/111.61
2 376/147
2 427/523
2 427/527
2 976/DIG 437

Titles of Most Frequently Occurring Classifications of Patents Returned
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- 11 250/423R (3 OR, 8 XR)
Class 250 : RADIANT ENERGY
250/423R ION GENERATION

- 10 315/111.81 (2 OR, 8 XR)
Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS
315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL
SUPPLY TO THE DISCHARGE SPACE
315/111.81 .Electron or ion source

- 7 313/359.1 (3 OR, 4 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/359.1 WITH POSITIVE OR NEGATIVE ION ACCELERATION

- 6 250/251 (4 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/251 ELECTRICALLY NEUTRAL MOLECULAR OR ATOMIC BEAM
DEVICES AND METHODS

- 6 313/231.31 (0 OR, 6 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/231.01 FLUENT MATERIAL SUPPLY OR FLOW DIRECTING MEANS
313/231.31 .Plasma

- 6 315/111.41 (0 OR, 6 XR)
Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS
315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL
SUPPLY TO THE DISCHARGE SPACE
315/111.21 .Plasma generating
315/111.41 ..With magnetic field

- 5 313/363.1 (1 OR, 4 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/359.1 WITH POSITIVE OR NEGATIVE ION ACCELERATION
313/363.1 .Extraction or target electrode

- 5 315/111.21 (2 OR, 3 XR)
Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS
315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL
SUPPLY TO THE DISCHARGE SPACE
315/111.21 .Plasma generating

- 5 315/111.31 (0 OR, 5 XR)
Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS
315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL
SUPPLY TO THE DISCHARGE SPACE
315/111.21 .Plasma generating
315/111.31 ..With extraction electrode

- 4 204/192.11 (2 OR, 2 XR)
Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY
204/192.1 .Coating, forming or etching by sputtering
204/192.11 ..Ion beam sputter deposition

- 4 204/298.04 (3 OR, 1 XR)
 Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY
 204/193 APPARATUS
 204/298.01 .Coating, forming or etching by sputtering
 204/298.02 ..Coating
 204/298.04 ...Ion beam sputter deposition
- 4 204/298.16 (0 OR, 4 XR)
 Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY
 204/193 APPARATUS
 204/298.01 .Coating, forming or etching by sputtering
 204/298.02 ..Coating
 204/298.16 ...Magnetically enhanced
- 4 250/427 (3 OR, 1 XR)
 Class 250 : RADIANT ENERGY
 250/423R ION GENERATION
 250/427 .Electron bombardment type
- 4 250/492.21 (2 OR, 2 XR)
 Class 250 : RADIANT ENERGY
 250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
 250/492.2 .Irradiation of semiconductor devices
 250/492.21 ..Ion bombardment
- 4 313/362.1 (0 OR, 4 XR)
 Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
 313/359.1 WITH POSITIVE OR NEGATIVE ION ACCELERATION
 313/362.1 .Supplying ionizable material (e.g., gas or vapor)
- 4 315/111.91 (2 OR, 2 XR)
 Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS
 315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL
 SUPPLY TO THE DISCHARGE SPACE
 315/111.81 .Electron or ion source
 315/111.91 ..Gas ionization type (e.g., ion pump or gauge source)
- 4 376/130 (1 OR, 3 XR)
 Class 376 : INDUCED NUCLEAR REACTIONS: PROCESSES, SYSTEMS, AND ELEMENTS
 376/100 NUCLEAR FUSION
 376/121 .Magnetic confinement of plasma
 376/127 ..With injection of electrically charged or accelerated particles
 376/130 ...Neutral particle injection
- 4 428/408 (1 OR, 3 XR)
 Class 428 : STOCK MATERIAL OR MISCELLANEOUS ARTICLES
 428/408 SELF-SUSTAINING CARBON MASS OR LAYER WITH IMPREGNANT OR OTHER LAYER
- 3 60/202 (2 OR, 1 XR)
 Class 060 : POWER PLANTS
 60/200.1 REACTION MOTOR (E.G., MOTIVE FLUID GENERATOR AND REACTION NOZZLE, ETC.)
 60/202 .Ion motor
- 3 204/298.19 (0 OR, 3 XR)
 Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY
 204/193 APPARATUS

- 204/298.01 .Coating, forming or etching by sputtering
- 204/298.02 ..Coating
- 204/298.16 ...Magnetically enhanced
- 204/298.17Flux passes through target surface
- 204/298.19Planar magnetron

- 3 250/398 (0 OR, 3 XR)
 - Class 250 : RADIANT ENERGY
 - 250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR FOCUSSING
 - 250/398 .With target means

- 3 313/360.1 (1 OR, 2 XR)
 - Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
 - 313/359.1 WITH POSITIVE OR NEGATIVE ION ACCELERATION
 - 313/360.1 .Plural apertured electrodes

- 3 427/580 (1 OR, 2 XR)
 - Class 427 : COATING PROCESSES
 - 427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC, WAVE, OR PARTICULATE ENERGY
 - 427/580 .Electrical discharge (e.g., arcs, sparks, etc.)

- 3 428/336 (1 OR, 2 XR)
 - Class 428 : STOCK MATERIAL OR MISCELLANEOUS ARTICLES
 - 428/221 WEB OR SHEET CONTAINING STRUCTURALLY DEFINED ELEMENT OR COMPONENT
 - 428/332 .Physical dimension specified
 - 428/334 ..Coating layer not in excess of 5 mils thick or equivalent
 - 428/335 ...Up to 3 mils
 - 428/3361 mil or less

- 3 428/694TC (0 OR, 3 XR)
 - Class 428 : STOCK MATERIAL OR MISCELLANEOUS ARTICLES
 - 428/411.1 COMPOSITE (NONSTRUCTURAL LAMINATE)
 - 428/688 .Of inorganic material
 - 428/689 ..Metal-compound-containing layer
 - 428/692 ...Defined magnetic layer
 - 428/694RDynamic recording medium
 - 428/694TMetal thin film magnetic layer
 - 428/694TPTopcoat, or protective overlayer
 - 428/694TCCarbon

- 2 118/723I (1 OR, 1 XR)
 - Class 118 : COATING APPARATUS
 - 118/715 GAS OR VAPOR DEPOSITION
 - 118/722 .With treating means (e.g., jarring)
 - 118/723R ..By creating electric field (e.g., gas activation, plasma, etc.)
 - 118/723I ...Radio frequency antenna or radio frequency inductive coil discharge means

- 2 156/345.39 (1 OR, 1 XR)
 - Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL MANUFACTURE
 - 156/345.1 DIFFERENTIAL FLUID ETCHING APPARATUS
 - 156/345.39 .With means to generate and to direct a reactive ion etchant beam at a workpiece

- 2 204/298.36 (0 OR, 2 XR)
 - Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY

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- 204/193 APPARATUS
- 204/298.01 .Coating, forming or etching by sputtering
- 204/298.31 ..Etching
- 204/298.36 ...Beam or directed flux etching (e.g., ion beam, etc.)

- 2 250/305 (0 OR, 2 XR)
 Class 250 : RADIANT ENERGY
 250/305 ELECTRON ENERGY ANALYSIS

- 2 250/397 (0 OR, 2 XR)
 Class 250 : RADIANT ENERGY
 250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR
 FOCUSING
 250/397 .With detector

- 2 250/492.2 (0 OR, 2 XR)
 Class 250 : RADIANT ENERGY
 250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
 250/492.2 .Irradiation of semiconductor devices

- 2 313/231.41 (0 OR, 2 XR)
 Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
 313/231.01 FLUENT MATERIAL SUPPLY OR FLOW DIRECTING MEANS

 313/231.31 .Plasma
 313/231.41 ..Arc discharge type

- 2 313/361.1 (0 OR, 2 XR)
 Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
 313/359.1 WITH POSITIVE OR NEGATIVE ION ACCELERATION
 313/361.1 .Means for deflecting or focusing

- 2 315/111.61 (0 OR, 2 XR)
 Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS

 315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL
 SUPPLY TO THE DISCHARGE SPACE
 315/111.21 .Plasma generating
 315/111.41 ..With magnetic field
 315/111.61 ...Acceleration

- 2 376/147 (0 OR, 2 XR)
 Class 376 : INDUCED NUCLEAR REACTIONS: PROCESSES,
 SYSTEMS, AND ELEMENTS
 376/100 NUCLEAR FUSION
 376/146 .Including removal or use of impurities or
 reaction products (e.g., energy)
 376/147 ..Direct conversion of energy

- 2 427/523 (1 OR, 1 XR)
 Class 427 : COATING PROCESSES
 427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,
 WAVE, OR PARTICULATE ENERGY
 427/523 .Ion plating or implantation

- 2 427/527 (0 OR, 2 XR)
 Class 427 : COATING PROCESSES
 427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,
 WAVE, OR PARTICULATE ENERGY
 427/523 .Ion plating or implantation
 427/527 ..Silicon present in substrate, plating, or
 implanted layer

2 976/DIG 437 (0 OR, 2 XR)
Class 976 : NUCLEAR TECHNOLOGY
976/DIG 427 ARRANGEMENTS FOR HANDLING RADIATION OR
PARTICLES (e.g., focusing, moderating [G21K-1/00] ***
(radiation filters DIG. 435)
976/DIG 437 .Using charge exchange devices (e.g., for
charges neutralizing or changing the sign of the electrical
of beams) [G21K-1/14] *** (producing or accelerating
neutral particle beams H05H-3/00).